

D E C L A R A T I O N

I, Kinshiro TSUKUDA, a national of Japan, c/o Sumitomo Chemical Intellectual Property Service, Limited, 5-33, Kitahama 4-chome, Chuo-ku, Osaka-shi, Osaka 541-8550, Japan, declare that to the best of my knowledge and belief the attached is a full, true and faithful translation into English made by me of the certified copy of Japanese Patent Application No. 2002-244971 attached thereto.

Signed this 17th day of January, 2005


Kinshiro TSUKUDA

Patent Application No. 2002-244971

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Applicant's Past Record

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JAPANESE PATENT OFFICE

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Commissioner,
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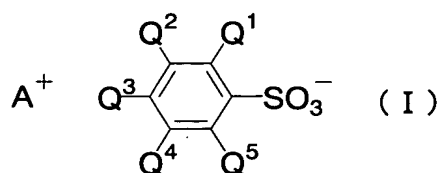
[DOCUMENT NAME] Specification

[TITLE OF THE INVENTION] ACID GENERATOR AND RESIST COMPOSITION

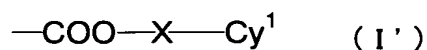
[SCOPE OF CLAIMS]

5 [Claim 1]

A salt of the formula (I):



wherein Q^1 , Q^2 , Q^3 , Q^4 and Q^5 each independently represent hydrogen,
optionally branched alkyl having 1 to 16 carbon atoms, optionally branched
10 alkoxy having 1 to 16 carbon atoms, halogen, aryl having 6 to 12 carbon atoms,
aralkyl having 7 to 12 carbon atoms, cyano, sulfide, hydroxy, nitro or a group of
the formula (I')



wherein X represents linear alkyl or linear alkyl optionally containing thioether
15 bond or ether bond, and Cy^1 represents alicyclic hydrocarbon group having 3 to
20 carbon atoms,
and A^+ represents a counter ion, with the proviso that at least one of Q^1 , Q^2 , Q^3 ,
 Q^4 and Q^5 is the group of the formula (I').

[Claim 2]

20 The salt according to Claim 1, wherein X is alkyl.

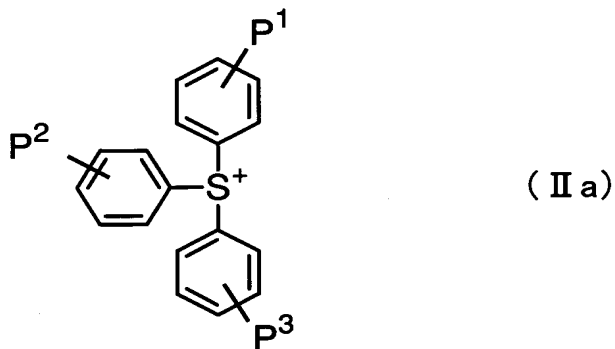
[Claim 3]

The salt according to Claim 1 or 2, wherein Cy^1 in the formula (I') is

cyclohexyl, 2-norbornan, 1-adamantyl or 2-adamantyl.

[Claim 4]

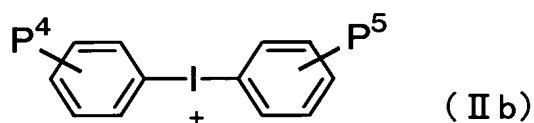
The salt according to any of Claims 1 to 3, wherein A^+ in the formula (I) is the formula (IIa)



wherein P^1 , P^2 and P^3 each independently represent hydrogen, hydroxyl, alkyl having 1 to 6 carbon atoms or alkoxy having 1 to 6 carbon atoms.

[Claim 5]

10 The salt according to any of Claims 1 to 3, wherein A^+ in the formula (I) is the formula (IIb)



wherein P^4 and P^5 each independently represent hydrogen, hydroxyl, alkyl having 1 to 6 carbon atoms or alkoxy having 1 to 6 carbon atoms.

[Claim 6]

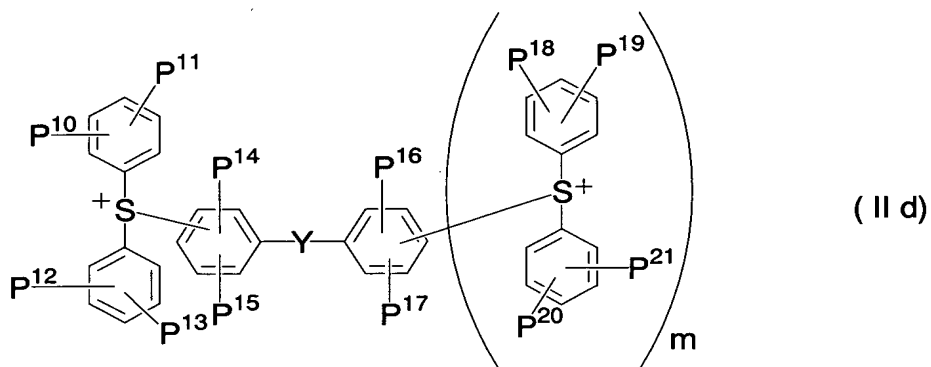
15 The salt according to any of Claims 1 to 3, wherein A^+ in the formula (I) is the formula (IIc)



wherein P⁶ and P⁷ each independently represent alkyl having 1 to 6 carbon atoms or cycloalkyl having 3 to 10 carbon atoms, or P⁶ and P⁷ bond to form alicyclic hydrocarbon group having 3 to 7 carbon atoms, said alicyclic hydrocarbon group may have ketone group, and at least one -CH₂- in the alicyclic hydrocarbon group may be substituted by oxygen or sulfur; P⁸ represents hydrogen, P⁹ represents alkyl having 1 to 6 carbon atoms, cycloalkyl having 3 to 10 carbon atoms or aromatic ring group optionally substituted, or P⁸ and P⁹ bond to form alicyclic hydrocarbon group.

10 [Claim 7]

The salt according to any of Claims 1 to 3, wherein A⁺ is the formula (II d)



wherein P¹⁰ to P²¹ each independently represent hydrogen, hydroxyl, alkyl having 1 to 6 carbon atoms or alkoxy having 1 to 6 carbon atoms, Y represents sulfur or oxygen, and m represents 0 or 1.

[Claim 8]

A chemical amplification type positive resist composition comprising resin which has a structural unit having an acid labile group and which itself is insoluble or poorly soluble in an alkali aqueous solution but becomes soluble in an alkali aqueous solution by the action of an acid, and a salt described in any of

5 Claims 1 to 7.

[Claim 9]

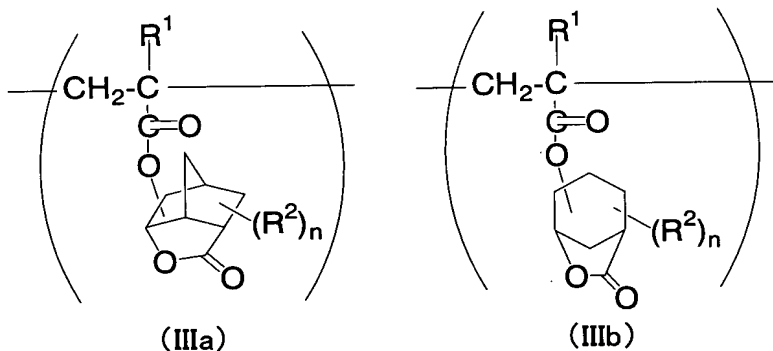
The composition according to Claim 8 wherein the content of the structural unit having an acid-labile group in all structural units of the resin is from 10 to 80%.

10 [Claim 10]

The composition according to Claim 8 or 9 wherein the structural unit having an acid-labile group is a structural unit derived from 2-alkyl-2-adamantyl (meth)acrylate or 1-(1-adamantyl)-1-alkylalkyl (meth)acrylate.

[Claim 11]

15 The composition according to any of Claims 8 to 10 wherein the resin contains, in addition to the structural unit having an acid-labile group, further at least one structural unit selected from the group consisting of a structural unit derived from p-hydroxystyrene, a structural unit derived from m-hydroxystyrene, a structural unit derived from 3-hydroxy-1-adamantyl
20 (meth)acrylate, a structural unit derived from 3,5-dihydroxy-1-adamantyl (meth)acrylate, a structural unit derived from (meth)acryloyloxy- γ -butyrolactone having a lactone ring optionally substituted by alkyl, a structural unit of the formula (IIIa) and a structural unit of the following formula (IIIb)



wherein R^1 and R^2 each independently represent hydrogen, methyl, trifluoromethyl or halogen, and n represents an integer of 1 to 3.

[Claim 12]

5 The composition according to any of Claims 9 to 11 wherein the resin further contains a structural unit derived from 2-norbornene and a structural unit derived from an aliphatic unsaturated dicarboxylic anhydride.

[Claim 13]

10 The composition according to any of Claims 8 to 12 wherein the composition further comprises amine as a quencher.

[Claim 14]

 The composition according to any of Claims 8 to 13 wherein the composition further comprises a surfactant.

[DETAILED DESCRIPTION OF THE INVENTION]

15 [0001]

[Technical Field Pertinent to the Invention]

 The present invention relates to a novel salt used in fine processing of semiconductors and resist composition containing the salt.

[0002]

[Prior Art]

Semiconductor microfabrication employs a lithography process using a resist composition. In lithography, theoretically, the shorter the exposure wavelength becomes, the higher the resolution can be made, as expressed by
5 Rayleigh's diffraction limit formula. The wavelength of an exposure light source for lithography used in the manufacture of semiconductor devices has been shortened year by year as g line having a wavelength of 436 nm, i line having a wavelength of 365 nm, KrF excimer laser having a wavelength of 248 nm and ArF excimer laser having a wavelength of 193 nm. F₂ excimer laser
10 having a wavelength of 157 nm seems to be promising as the next-generation exposure light source. Further, as the exposure light source of the subsequent generation, soft X ray (EUV) having a wavelength of 13 nm or shorter has been proposed as the exposure light source following the 157nm-wavelength F₂ excimer laser.

15 [0003]

Since light sources having shorter wavelength than that of g line and i line, such as excimer laser and the like have low illumination, it is necessary to enhance the sensitivity of a resist. Consequently, there are used so-called chemical amplification type resists utilizing the catalytic action of an acid
20 produced from a sulfonium salt, iodonium salt, and the like by exposure and containing a resin having a group being dissociated by this acid.

[0004]

However, in conventionally known chemical amplification type resist compositions, there is a problem that line edge roughness occurs by generation

of standing wave and the like, namely, smoothness on a pattern side wall decreases, and resultantly, uniformity of line width deteriorates.

[0005]

Though it is known that the use of an acid generator including anion of benzenesulfonic acid having at least one ester group in a positive type photosensitive composition (JP-H09-244234-A), it is still difficult to combine progress of roughness and progress of pattern shapes.

[0006]

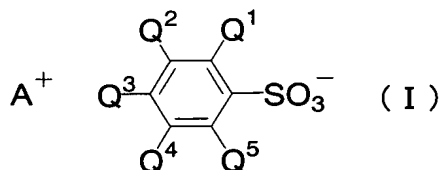
[Problems to be solved by the Invention]

An object of the present invention is to provide a novel salt used for chemical amplification type resist and to provide a chemical amplification type resist composition comprising the above-mentioned salt and a resin component, and suitable for excimer laser lithography using ArF, KrF, and the like, showing excellent various resist abilities such as sensitivity, resolution and the like, and giving particularly improved line edge roughness and pattern profiles.

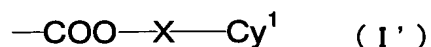
[0007]

The present inventors have conducted extensive studies, and as a result, has found that a chemical amplification type positive resist composition using a specific benzenesulfonate anion derivative provides patterns showing excellent various resist abilities such as sensitivity, resolution and the like, and giving particularly improved line edge roughness and pattern profiles, and thus the present invention was completed.

That is, the present invention relates to
<1>alt of the following formula (I):



wherein Q^1 , Q^2 , Q^3 , Q^4 and Q^5 each independently represent hydrogen,
optionally branched alkyl having 1 to 16 carbon atoms, optionally branched
alkoxy having 1 to 16 carbon atoms, halogen, aryl having 6 to 12 carbon atoms,
5 aralkyl having 7 to 12 carbon atoms, cyano, sulfide, hydroxy, nitro or a group of
the formula (I')

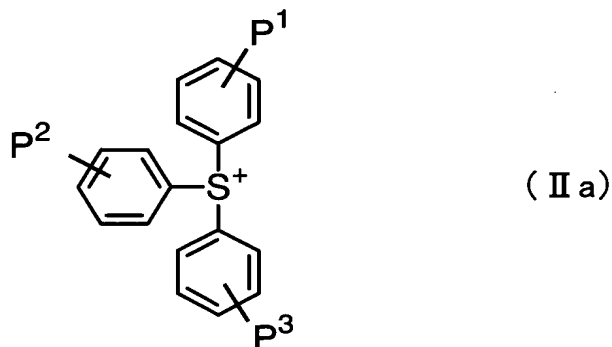


wherein X represents linear alkyl or linear alkyl optionally containing thioether
bond or ether bond, and Cy^1 represents alicyclic hydrocarbon group having 3 to
10 20 carbon atoms,
and A^+ represents a counter ion, with the proviso that at least one of Q^1 , Q^2 , Q^3 ,
 Q^4 and Q^5 is the group of the formula (I').

[0008]

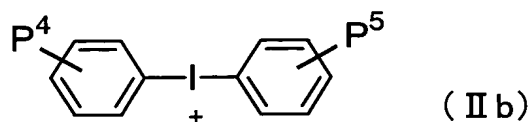
The present invention also relates to

15 <2> a salt wherein, in the formula (I), A^+ is the formula (IIa), (IIb), (IIc) or (IId):

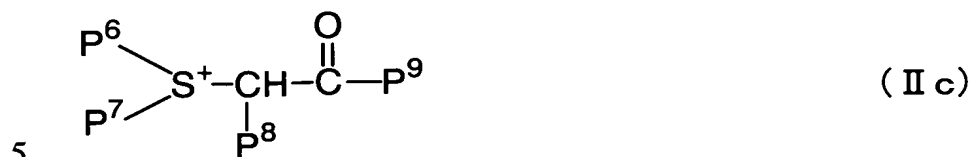


wherein P^1 , P^2 and P^3 each independently represent hydrogen, hydroxyl, alkyl

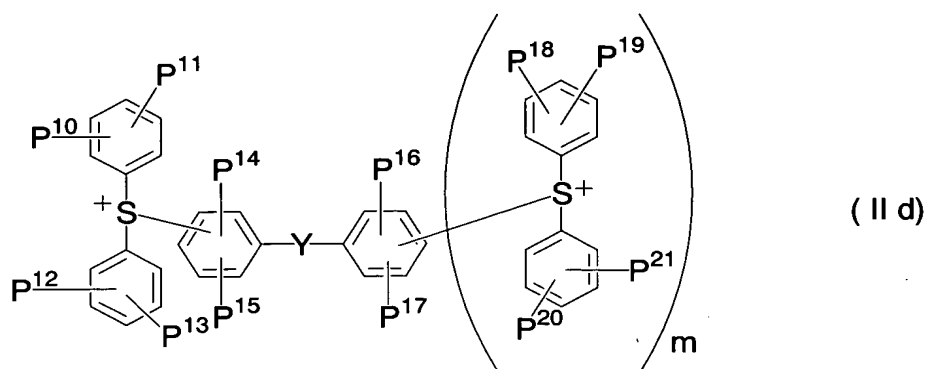
having 1 to 6 carbon atoms or alkoxy having 1 to 6 carbon atoms;



wherein P^4 and P^5 each independently represent hydrogen, hydroxyl, alkyl having 1 to 6 carbon atoms or alkoxy having 1 to 6 carbon atoms;



wherein P^6 and P^7 each independently represent alkyl having 1 to 6 carbon atoms or cycloalkyl having 3 to 10 carbon atoms, or P^6 and P^7 bond to form alicyclic hydrocarbon group having 3 to 7 carbon atoms, said alicyclic hydrocarbon group may have ketone group, and at least one $-CH_2-$ in the alicyclic hydrocarbon group may be substituted by oxygen or sulfur; P^8 represents hydrogen, P^9 represents alkyl having 1 to 6 carbon atoms, cycloalkyl having 3 to 10 carbon atoms or aromatic ring group optionally substituted, or P^8 and P^9 bond to form alicyclic hydrocarbon group;



wherein P^{10} to P^{21} each independently represent hydrogen, hydroxyl, alkyl having 1 to 6 carbon atoms or alkoxy having 1 to 6 carbon atoms, Y represents

sulfur or oxygen, and m represents 0 or 1.

[0009]

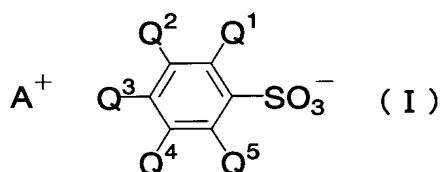
The present invention further relates to

- <3> a chemical amplification type positive resist composition comprising resin
 5 which has a structural unit having an acid labile group and which itself is insoluble or poorly soluble in an alkali aqueous solution but becomes soluble in an alkali aqueous solution by the action of an acid, and a salt described in <1> or <2> above.

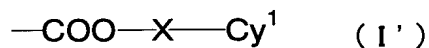
[0010]

- 10 [Mode for carrying out the Invention]

The present salt is represented by the following formula (I):



- wherein Q^1 , Q^2 , Q^3 , Q^4 and Q^5 each independently represent hydrogen,
 optionally branched alkyl having 1 to 16 carbon atoms, optionally branched
 15 alkoxy having 1 to 16 carbon atoms, halogen, aryl having 6 to 12 carbon atoms, aralkyl having 7 to 12 carbon atoms, cyano, sulfide, hydroxy, nitro or a group of the formula (I')



- wherein X represents linear alkyl or linear alkyl optionally containing thioether
 20 bond or ether bond, and Cy^1 represents alicyclic hydrocarbon group having 3 to 20 carbon atoms,
 and A^+ represents a counter ion, with the proviso that at least one of Q^1 , Q^2 , Q^3 ,

Q^4 and Q^5 is the group of the formula (I').

Examples of the optionally branched alkyl having 1 to 16 carbon atoms include methyl, ethyl, propyl, isopropyl, butyl, tert-butyl, pentyl, hexyl, octyl, decyl, dodecyl, hexadecyl, and the like.

5 Examples of the optionally branched alkoxy having 1 to 16 carbon atoms include methoxy, ethoxy, propoxy, isopropoxy, butoxy, tert-butoxy, pentyloxy, hexyloxy, isopentyloxy, decyloxy, dodecyloxy, hexadecyloxy, and the like.

Examples of halogen include fluorine, chlorine, bromine and iodine.

10 Examples of aryl having 6 to 12 carbon atoms include phenyl, tolyl, methoxyphenyl, naphthyl and the like.

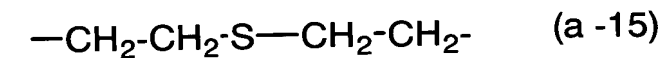
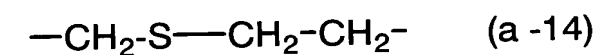
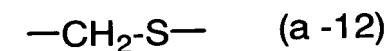
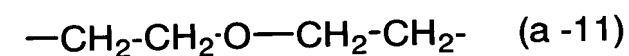
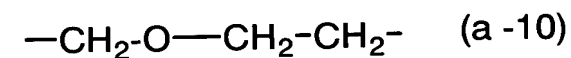
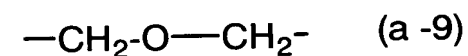
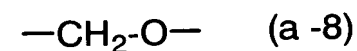
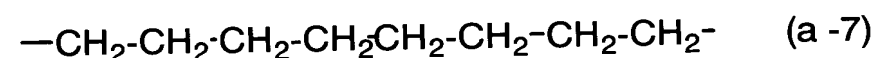
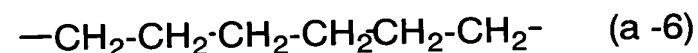
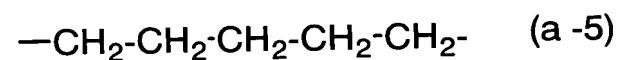
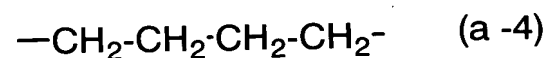
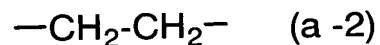
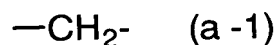
Examples of the aralkyl having 7 to 12 carbon atoms include benzyl, chlorobenzyl, methoxybenzyl, and the like.

[0011]

15 When two or more of Q^1 , Q^2 , Q^3 , Q^4 and Q^5 are the groups of the formula (I'), the groups of the formula (I') may independently be selected.

[0012]

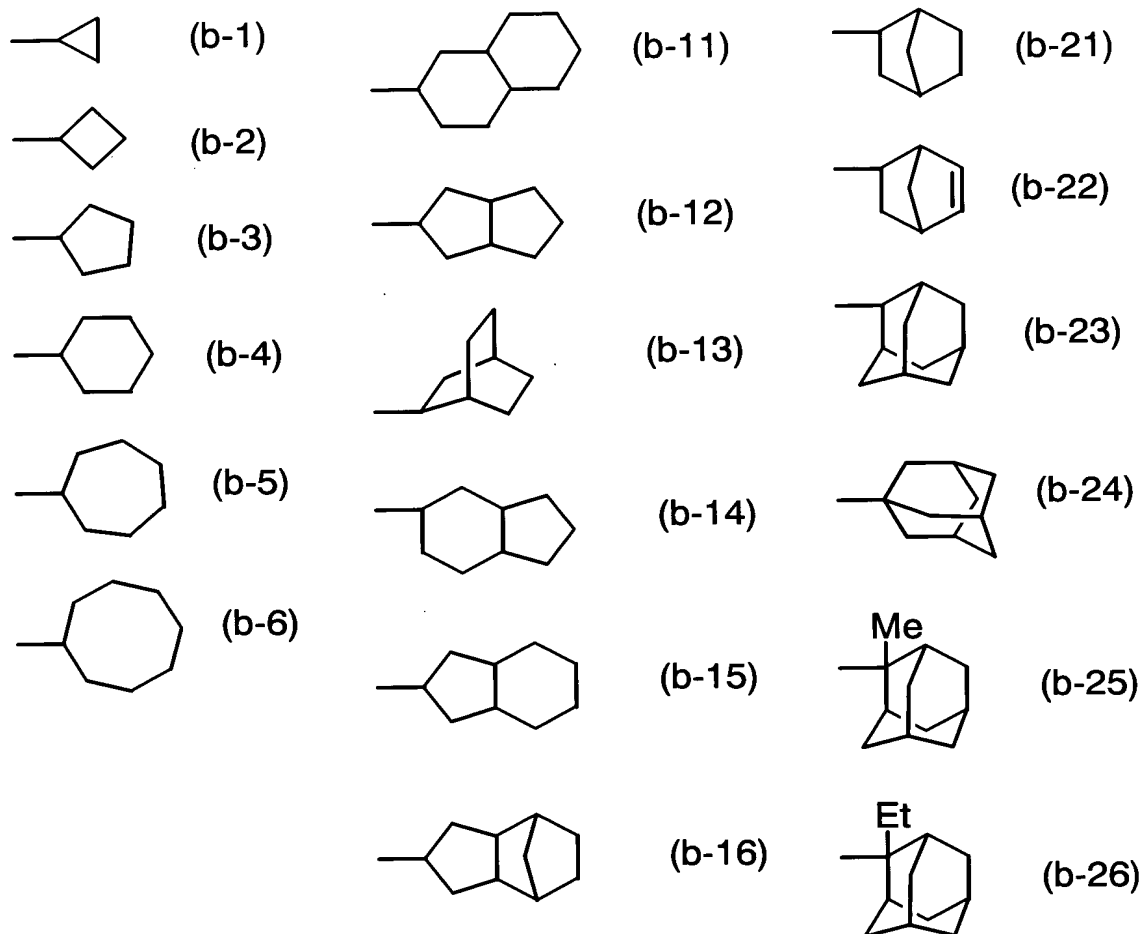
Examples of X include the followings:



In the formulae above, linear alkyl of (a-1) to (a-7) are preferred.

[0013]

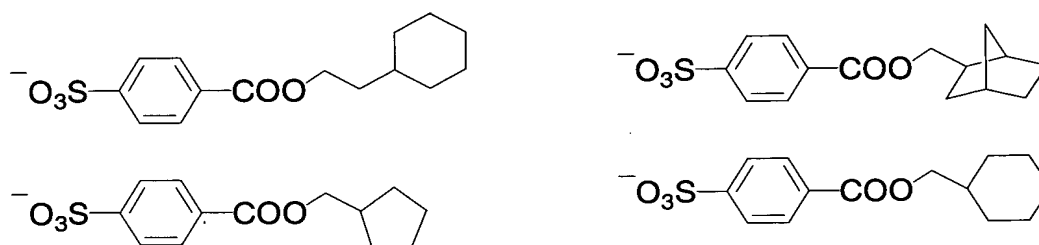
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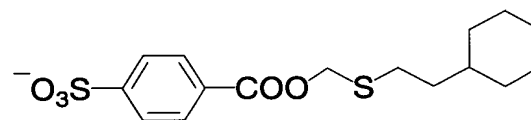
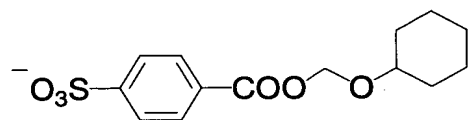
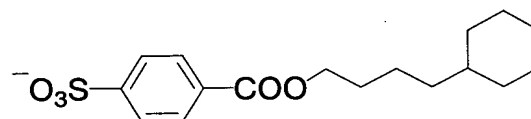
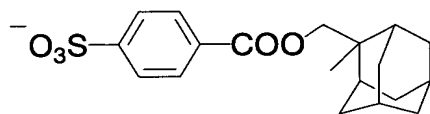
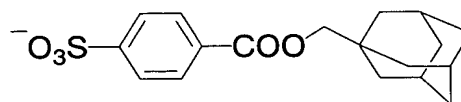
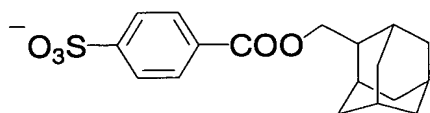


In the formulae above, cyclohexyl (b-4), 2-norbornyl (b-21), 1-adamantyl (b-24) and 2-adamantyl (b-23) are preferred.

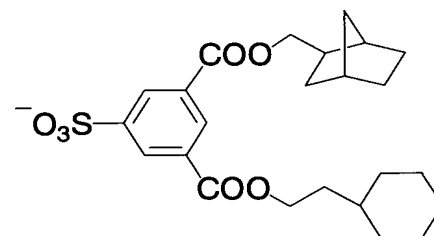
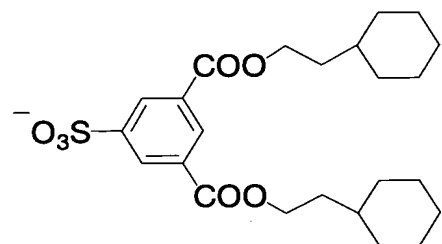
[0014]

- 5 Specific examples of the anion part in the salt of the formula (I) include the followings:

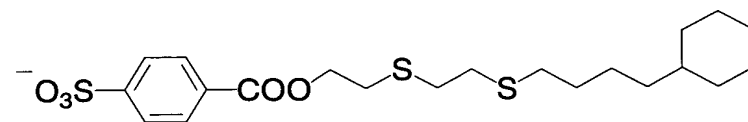
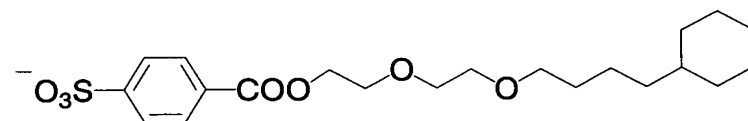
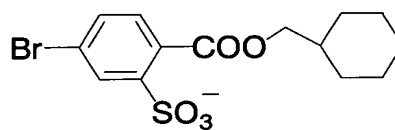
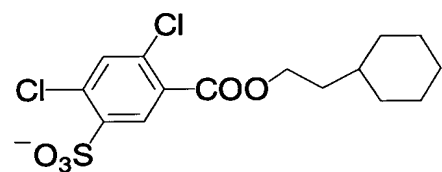




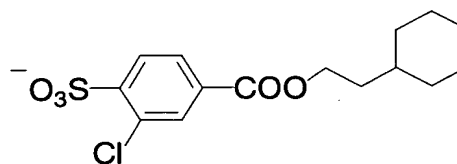
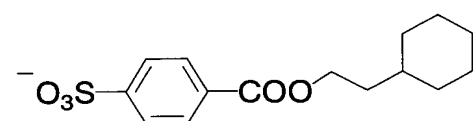
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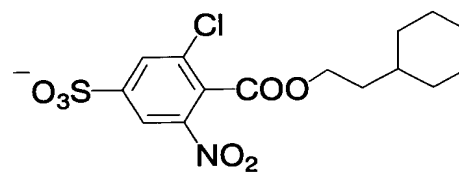
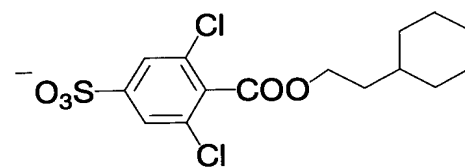
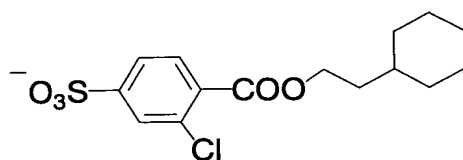
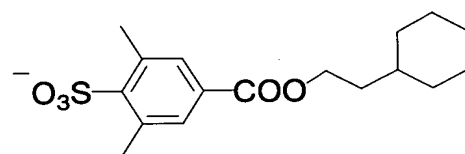
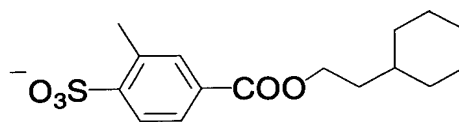
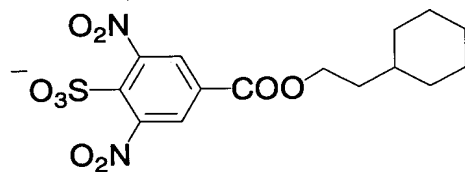
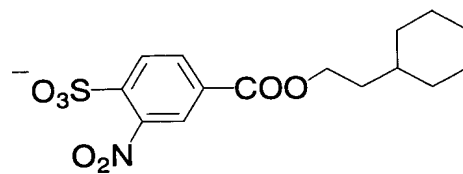
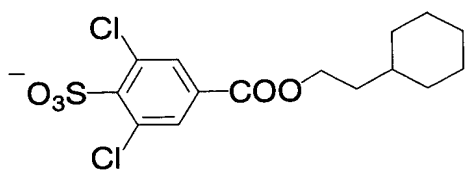
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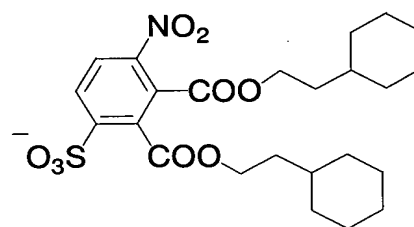
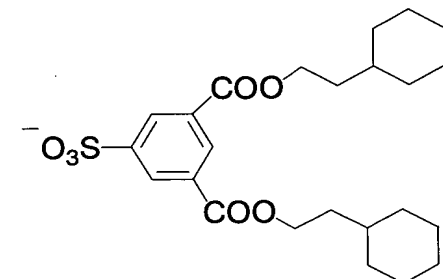
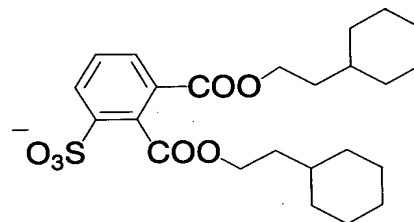
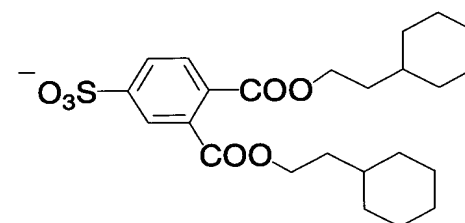
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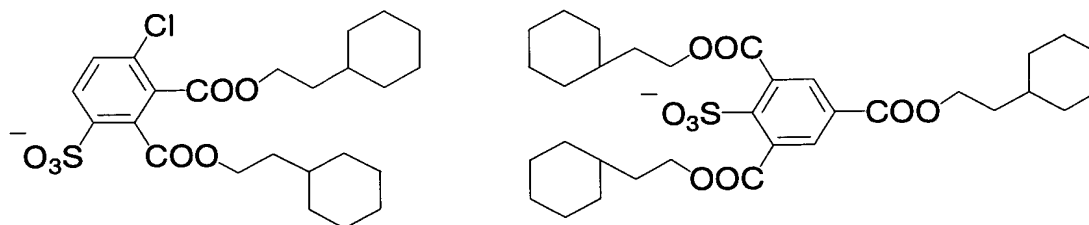


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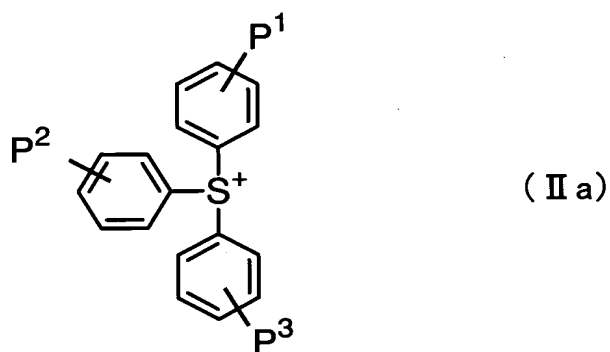
5 [0017]





[0018]

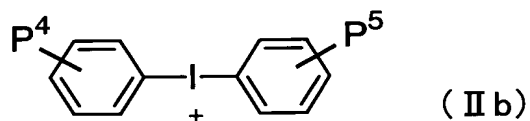
Examples of the salt of the formula (I) include salts wherein A^+ is the formula (IIa), (IIb), (IIc) or (IId):



5

wherein P^1 , P^2 and P^3 each independently represent hydrogen, hydroxyl, alkyl having 1 to 6 carbon atoms or alkoxy having 1 to 6 carbon atoms;

[0019]



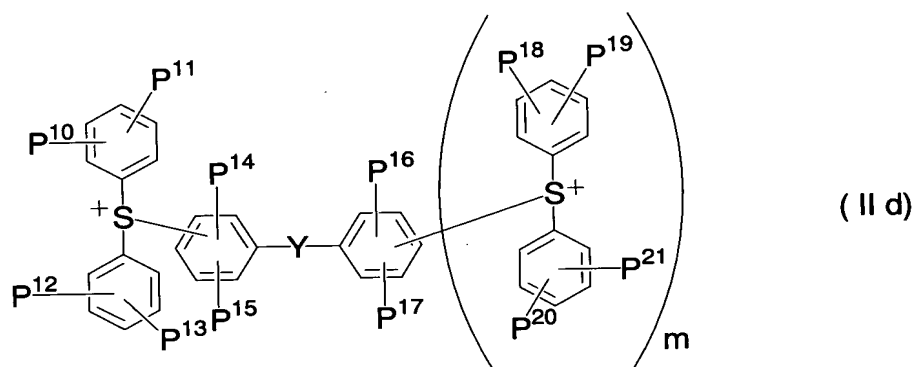
10 wherein P^4 and P^5 each independently represent hydrogen, hydroxyl, alkyl having 1 to 6 carbon atoms or alkoxy having 1 to 6 carbon atoms;

[0020]



wherein P^6 and P^7 each independently represent alkyl having 1 to 6 carbon atoms or cycloalkyl having 3 to 10 carbon atoms, or P^6 and P^7 bond to form alicyclic hydrocarbon group having 3 to 7 carbon atoms, said alicyclic hydrocarbon group may have ketone group, and at least one $-CH_2-$ in the alicyclic hydrocarbon group may be substituted by oxygen or sulfur; P^8 represents hydrogen, P^9 represents alkyl having 1 to 6 carbon atoms, cycloalkyl having 3 to 10 carbon atoms or aromatic ring group optionally substituted, or P^8 and P^9 bond to form alicyclic hydrocarbon group;

[0021]



10

wherein P^{10} to P^{21} each independently represent hydrogen, hydroxyl, alkyl having 1 to 6 carbon atoms or alkoxy having 1 to 6 carbon atoms, Y represents sulfur or oxygen, and m represents 0 or 1.

[0022]

15 In the formula (IIa), P^1 , P^2 and P^3 each independently represent hydrogen, hydroxyl, alkyl having 1 to 6 carbon atoms or alkoxy having 1 to 6 carbon atoms, and the alkyl and alkoxy may be linear or branched in the case of 3 or more carbon atoms.

In the formula (IIb), P^4 and P^5 each independently represent hydrogen,

hydroxyl, alkyl having 1 to 6 carbon atoms or alkoxy having 1 to 6 carbon atoms, and the alkyl and alkoxy may be linear or branched in the case of 3 or more carbon atoms.

In P¹, P², P³, P⁴ and P⁵, specific examples of the alkyl include methyl, ethyl, propyl, isopropyl, butyl, tert-butyl, pentyl, hexyl and the like, and examples of the alkoxy include methoxy, ethoxy, propoxy, butoxy and the like.
[0023]

In the formula (IIc), P⁶ and P⁷ each independently represent alkyl having 1 to 6 carbon atoms or cycloalkyl having 3 to 10 carbon atoms, or alicyclic hydrocarbon group having 3 to 7 carbon atoms. Said alicyclic hydrocarbon group may have carbonyl group. At least one -CH₂- in the alicyclic hydrocarbon group may be substituted by oxygen or sulfur.

P⁸ represents hydrogen and P⁹ represents alkyl having 1 to 6 carbon atoms, cycloalkyl having 3 to 10 carbon atoms or aromatic ring group optionally substituted, or P⁸ and P⁹ bond to form alicyclic hydrocarbon group.

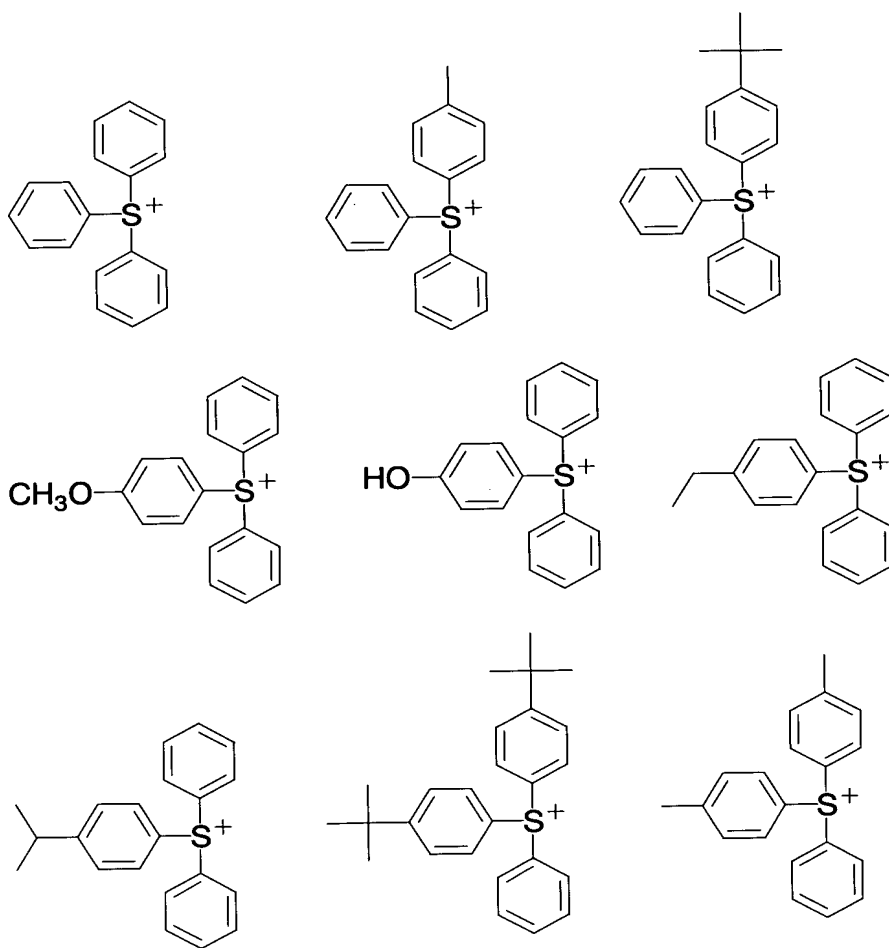
Specific examples of the alkyl include methyl, ethyl, propyl, isopropyl, butyl, tert-butyl, pentyl, hexyl and the like, and specific examples of the cycloalkyl include cyclopropyl, cyclobutyl, cyclopentyl, cyclohexyl, cycloheptyl and the like.
[0024]

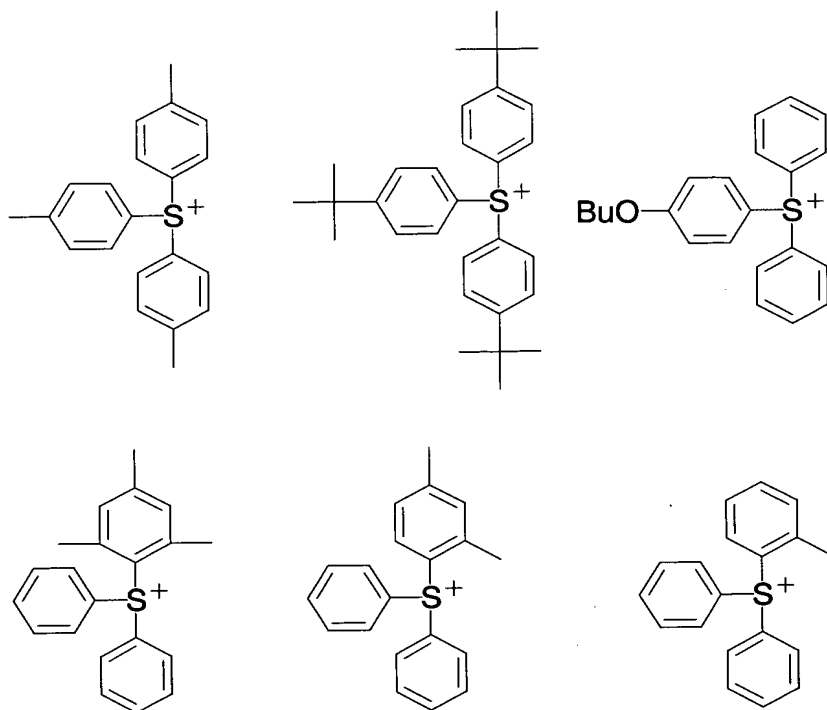
In the formula (IId), P¹⁰ to P²¹ each independently represent hydrogen, hydroxyl, alkyl having 1 to 6 carbon atoms or alkoxy having 1 to 6 carbon atoms. The alkyl and alkoxy may be linear or branched in the case of 3 or more carbon atoms. Specific examples of the alkyl include methyl, ethyl, propyl, isopropyl,

butyl, tert-butyl, pentyl, hexyl and the like, and examples of the alkoxy include methoxy, ethoxy, propoxy, butoxy and the like. Y represents sulfur or oxygen. m represents 0 or 1.

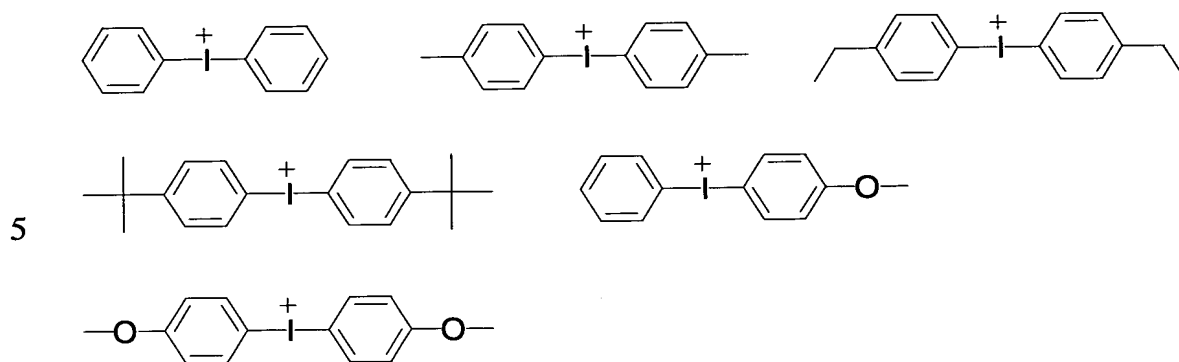
[0025]

- 5 Specific examples of the counter ion represented by A^+ in the salt of the formula (I) include the followings:

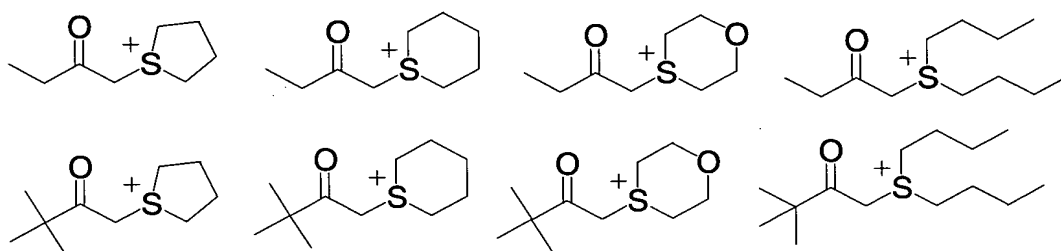


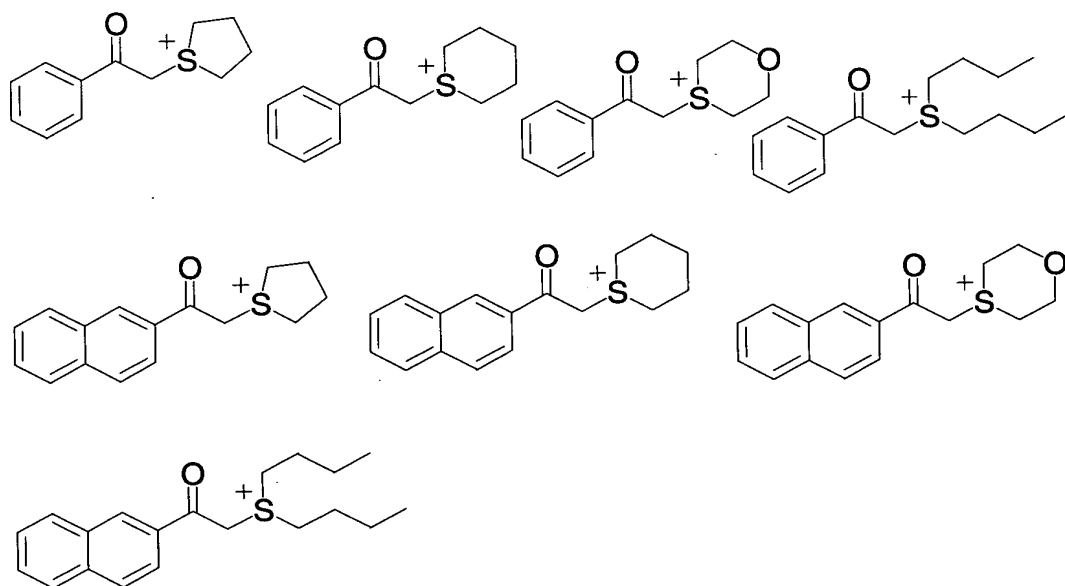


[0026]



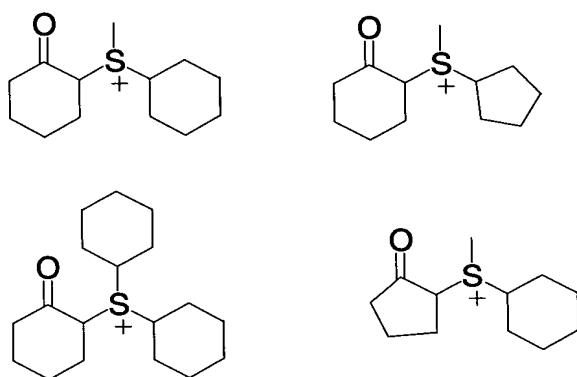
[0027]





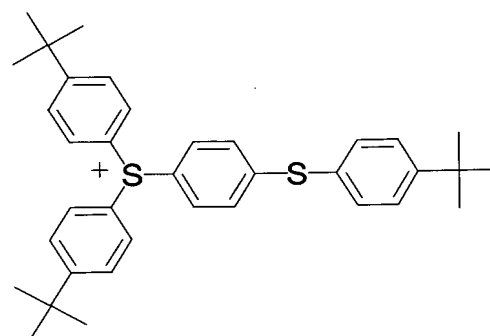
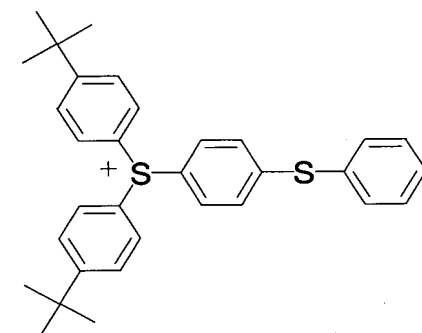
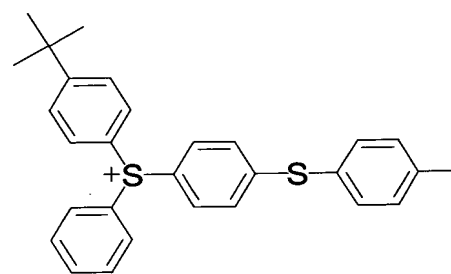
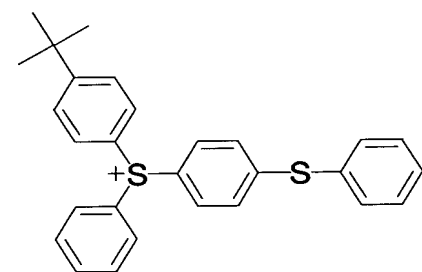
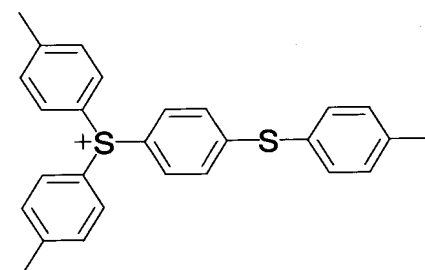
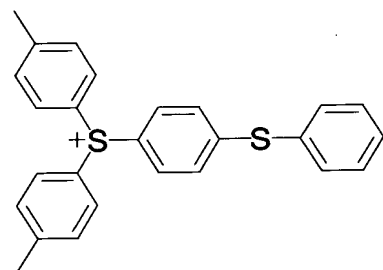
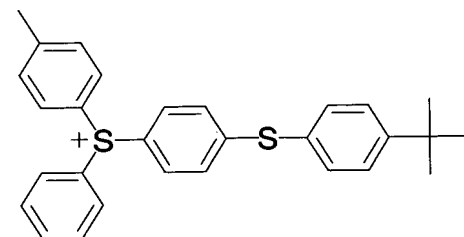
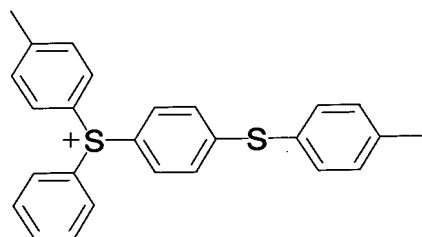
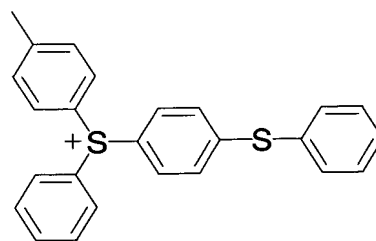
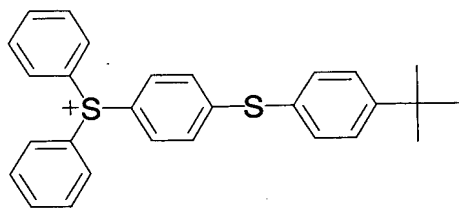
[0028]

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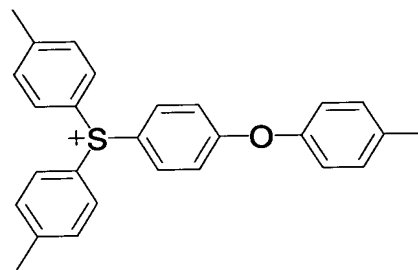
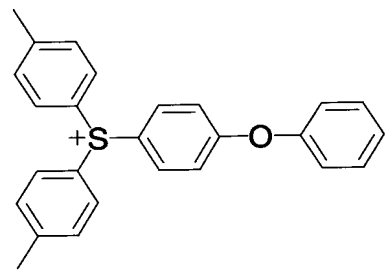
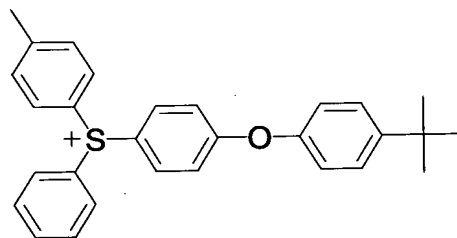
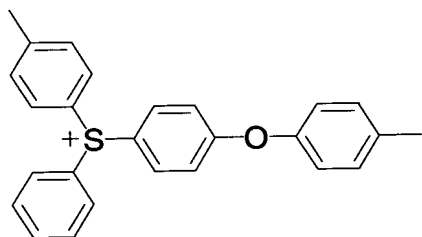
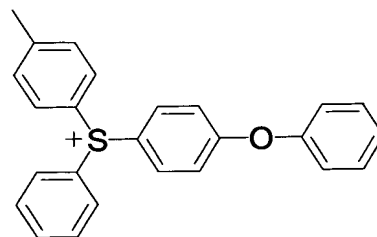
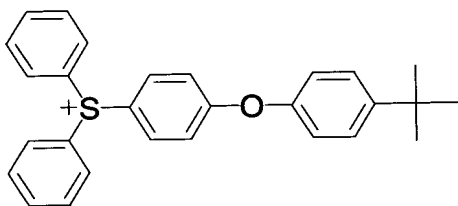
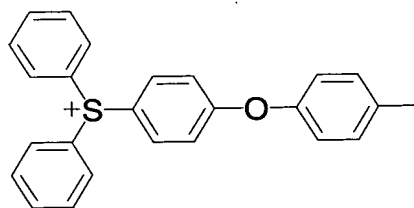
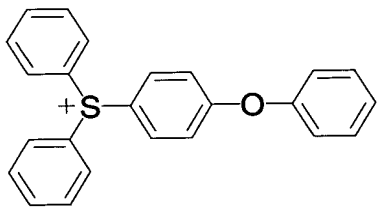


[0029]

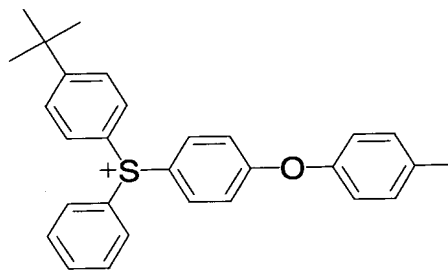
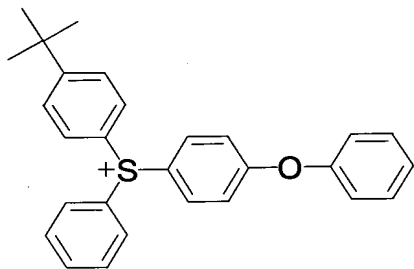


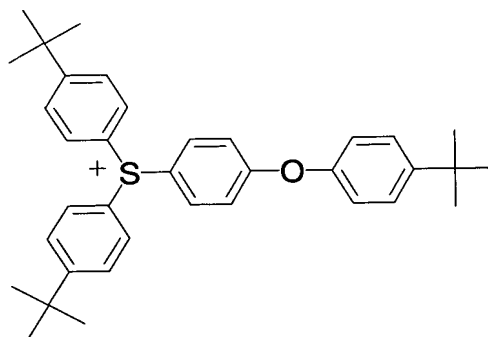


[0030]

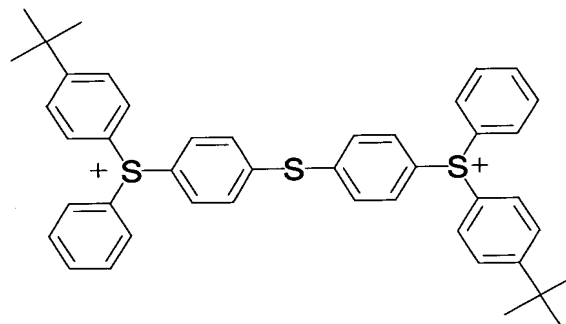
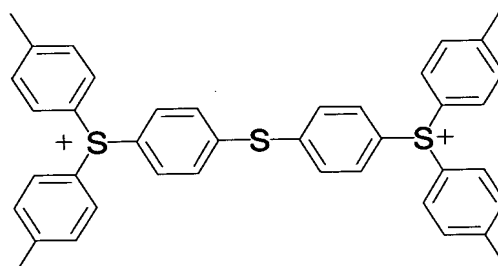


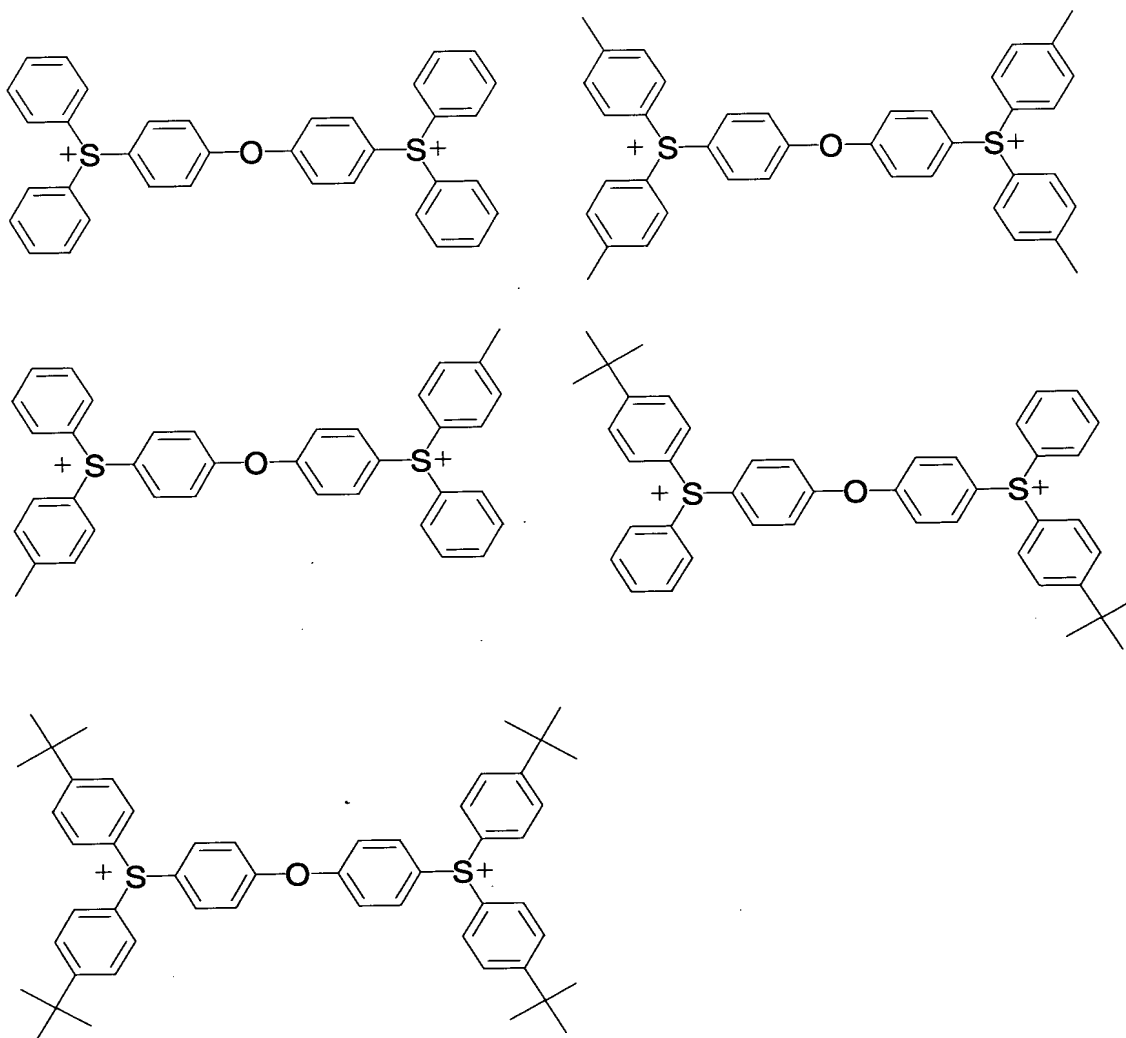
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[0031]





[0032]

- 5 The chemical amplification type positive resist composition of the present invention comprises resin which contains a structural unit having an acid labile group and which itself is insoluble or poorly soluble in an alkali aqueous solution but becomes soluble in an alkali aqueous solution by the action of an acid, and the salt represented by the formula (I) described above.

10 [0033]

As salt of the formula (I) in the present composition, salt wherein A^+ is the formula (IIa), salt wherein A^+ is the formula (IIb), salt wherein A^+ is the

formula (IIc) and salt wherein A^+ is the formula (IIa) are preferred.

In the formula (IIa), P^1 , P^2 and P^3 each independently represent hydrogen, hydroxyl, alkyl having 1 to 6 carbon atoms or alkoxy having 1 to 6 carbon atoms, and the alkyl and alkoxy may be linear or branched in the case of 3 or more
5 carbon atoms.

In the formula (IIb), P^4 and P^5 each independently represent hydrogen, hydroxyl, alkyl having 1 to 6 carbon atoms or alkoxy having 1 to 6 carbon atoms, and the alkyl and alkoxy may be linear or branched in the case of 3 or more carbon atoms.

10 In P^1 , P^2 , P^3 , P^4 and P^5 , specific examples of the alkyl include methyl, ethyl, propyl, isopropyl, butyl, tert-butyl, pentyl, hexyl and the like, and examples of the alkoxy include methoxy, ethoxy, propoxy, butoxy and the like.
[0034]

In the formula (IIc), P^6 and P^7 each independently represent alkyl having
15 1 to 6 carbon atoms or cycloalkyl having 3 to 10 carbon atoms, or P^6 and P^7 bond to form alicyclic hydrocarbon group having 3 to 7 carbon atoms. Said alicyclic hydrocarbon group may have carbonyl group. At least one $-CH_2-$ in the alicyclic hydrocarbon group may be substituted by oxygen or sulfur.

P^8 represents hydrogen and P^9 represents alkyl having 1 to 6 carbon
20 atoms, cycloalkyl having 3 to 10 carbon atoms or aromatic ring group optionally substituted, or P^8 and P^9 bond to form alicyclic hydrocarbon group.

Specific examples of the alkyl include methyl, ethyl, propyl, isopropyl, butyl, tert-butyl, pentyl, hexyl and the like, and specific examples of the cycloalkyl include cyclopropyl, cyclobutyl, cyclopentyl, cyclohexyl,

cycloheptyl and the like.

[0035]

In the formula (IId), P^{10} to P^{21} each independently represent hydrogen, hydroxyl, alkyl having 1 to 6 carbon atoms or alkoxy having 1 to 6 carbon atoms.

- 5 The alkyl and alkoxy may be linear or branched in the case of 3 or more carbon atoms. Specific examples of the alkyl include methyl, ethyl, propyl, isopropyl, butyl, tert-butyl, pentyl, hexyl and the like, and examples of the alkoxy include methoxy, ethoxy, propoxy, butoxy and the like. Y represents sulfur or oxygen. m represents 0 or 1.

10 [0036]

- Next, resin components constituting the present composition will be explained. The resin used in the present composition contains a structural unit having an acid-labile group. The resin for the chemical amplification type positive resist composition is insoluble or poorly soluble itself in alkali aqueous solution and shows partial dissociation of groups by the action of an acid to become soluble in alkali aqueous solution after the dissociation. The acid-labile group can be selected from conventionally known various groups.
- 15

- Specifically, various esters of carboxylic acids are mentioned as the acid-labile group, and examples thereof include alky esters such as methyl ester and tert-butyl ester; acetal type esters such as methoxymethyl ester, ethoxymethyl ester, 1-ethoxyethyl ester, 1-isobutoxyethyl ester, 1-isopropoxyethyl ester, 1-ethoxypropyl ester, 1-(2-methoxyethoxy)ethyl ester, 1-(2-acetoxyethoxy)ethyl ester, 1-[2-(1-adamantyloxy)ethoxy]ethyl ester, 1-[2-(1-adamantanecarbonyloxy)ethoxy]ethyl ester, tetrahydro-2-furyl ester and
- 20

tetrahydro-2-pyranyl ester; alicyclic esters such as isobornyl ester, 2-alkyl-2-adamantyl ester, 1-(1-adamantyl)-1-alkylalkyl ester, and the like.

Monomers leading to structural units having such ester of carboxylic acid may be (meth)acryl-based monomers such as methacrylates and acrylates, or those obtained by bonding of a ester group of carboxylic acid to alicyclic monomer such as norbornenecarboxylate, tricyclodecenecarboxylate and tetracyclodecenecarboxylate.

[0037]

Among the above-mentioned monomers, it is preferable to use those having a bulky group containing alicyclic group such as, for example, 2-alkyl-2-adamantyl and 1-(1-adamantyl)-1-alkylalkyl, as the group dissociated by the action of an acid, since excellent resolution is obtained.

Examples of such monomer containing a bulky group include 2-alkyl-2-adamantyl (meth)acrylate, 1-(1-adamantyl)-1-alkylalkyl (meth)acrylate, 2-alkyl-2-adamantyl 5-norbornene-2-carboxylate, 1-(1-adamantyl)-1-alkylalkyl 5-norbornene-2-carboxylate, and the like.

Particularly when 2-alkyl-2-adamantyl (meth)acrylate or 2-alkyl-2-adamantyl α -chloroacrylate is used as the monomer, it is preferred because excellent resolution is obtained. Typical examples of such 2-alkyl-2-adamantyl (meth)acrylate and 2-alkyl-2-adamantyl α -chloroacrylate include 2-methyl-2-adamantyl acrylate, 2-methyl-2-adamantyl methacrylate, 2-ethyl-2-adamantyl acrylate, 2-ethyl-2-adamantyl methacrylate, 2-n-butyl-2-adamantyl acrylate, 2-methyl-2-adamantyl α -chloroacrylate, 2-ethyl-2-adamantyl α -chloroacrylate and the like. When particularly

2-ethyl-2-adamantyl (meth)acrylate or 2-ethyl-2-adamantyl α -chloroacrylate is used, it is preferred because balance between sensitivity and heat resistance is excellent. In the present invention, other monomer having group dissociated by the action of an acid may be used together, if necessary.

5 [0038]

2-alkyl-2-adamantyl (meth)acrylate can usually be produced by reacting 2-alkyl-2-adamantanol or metal salt thereof with an acrylic halide or methacrylic halide.

[0039]

10 The resin used for the present composition can also contain, in addition to the above-mentioned structural units having an acid-labile group, other structural units not dissociated or not easily dissociated by the action of an acid. Examples of such other structural units which can be contained include structural units of monomers having a free carboxyl group such as acrylic acid
15 and methacrylic acid, structural units of aliphatic unsaturated dicarboxylic anhydrides such as maleic anhydride and itaconic anhydride, structural unit of 2-norbornene, structural unit of (meth)acrylonitrile, structural unit of various (meth)acrylate, and the like.

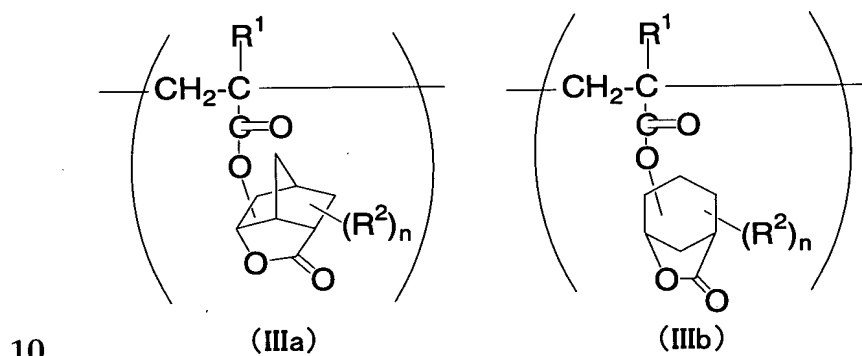
20 Though it is not preferred in the case of ArF exposure because of its large light absorption, there is no problem on light absorption in the case of KrF exposure and a structural unit of hydroxystyrene can be further contained.

[0040]

Particularly, to contain, in addition to the structural unit having an acid-labile group, further at least one structural unit selected from the group

consisting of a structural unit derived from p-hydroxystyrene, a structural unit derived from m-hydroxystyrene, a structural unit derived from 3-hydroxy-1-adamantyl (meth)acrylate, a structural unit derived from 3,5-dihydroxy-1-adamantyl (meth)acrylate, a structural unit derived from (meth)acryloyloxy- γ -butyrolactone having a lactone ring optionally substituted by alkyl, a structural unit of the following formula (IIIa) and a structural unit of the following formula (IIIb), in the resin in the present composition, is preferable from the standpoint of the adhesiveness of resist to a substrate.

[0041]



In the formulae (IIIa) and (IIIb), R^1 and R^2 each independently represent hydrogen, methyl, trifluoromethyl or halogen, and n represents an integer of 1 to 3.

[0042]

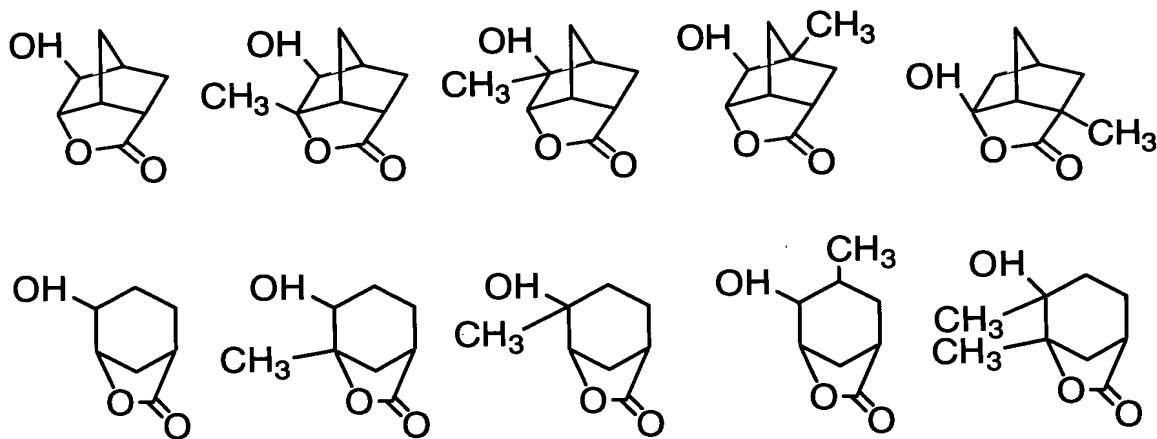
15 3-Hydroxy-1-adamantyl (meth)acrylate and 3,5-dihydroxy-1-adamantyl (meth)acrylate can be produced by, for example, reacting corresponding hydroxyadamantane with (meth)acrylic acid or its acid halide, and they are also commercially available.

Further, (meth)acryloyloxy- γ -butyrolactone can be produced by

reacting α - or β -bromo- γ -butyrolactone having a lactone ring optionally substituted by alkyl with acrylic acid or methacrylic acid, or reacting α - or β -bromo- γ -butyrolactone having a lactone ring optionally substituted by alkyl with acrylic halide or methacrylic halide.

- 5 As monomers leading to structural units of the formulae (IIIa) and (IIIb), specifically listed are, for example, (meth)acrylates of alicyclic lactones having hydroxyl described below, and mixtures thereof, and the like. These esters can be produced, for example, by reacting corresponding alicyclic lactone having hydroxyl with (meth)acrylic acids, and the production method thereof is
- 10 described in, for example, JP2000-26446-A.

[0043]



[0044]

- 15 When any of the structural unit derived from 3-hydroxy-1-adamantyl (meth)acrylate, the structural unit derived from 3,5-dihydroxy-1-adamantyl (meth)acrylate, the structural unit derived from α -(meth)acryloyloxy- γ -butyrolactone, the structural unit derived from β -(meth)acryloyloxy- γ -butyrolactone and the structural unit of the formulae (IIIa) and (IIIb) is

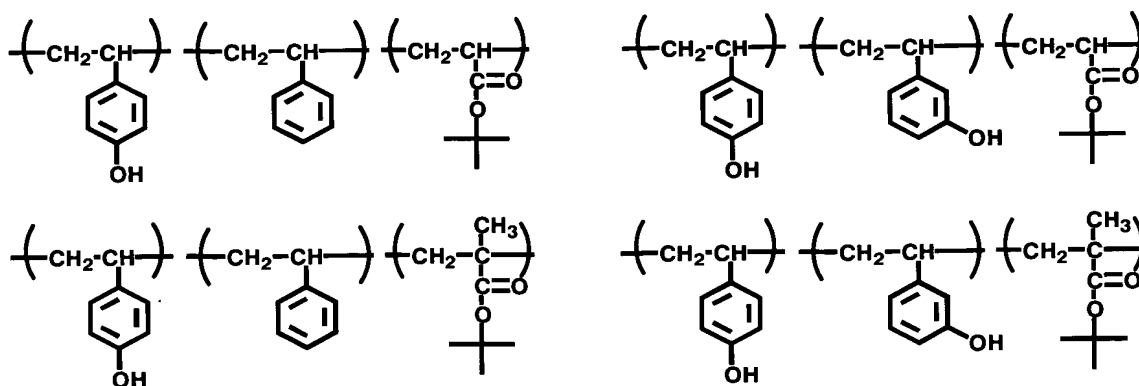
contained in the resin, not only the adhesiveness of the resist to a substrate is improved, but also the resolution of the resist is improved.

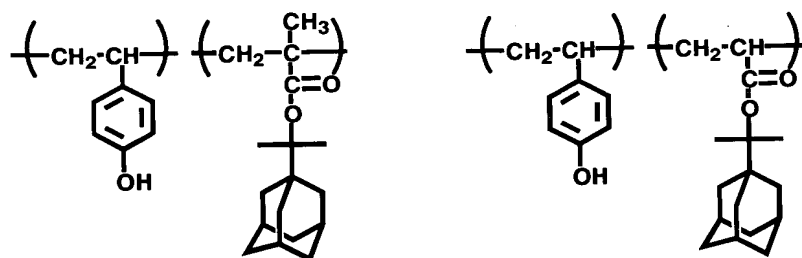
[0045]

Here, examples of the (meth)acryloyloxy- γ -butyrolactone include α -acryloyloxy- γ -butyrolactone, α -methacryloyloxy- γ -butyrolactone, α -acryloyloxy- β , β -dimethyl- γ -butyrolactone, α -methacryloyloxy- β , β -dimethyl- γ -butyrolactone, α -acryloyloxy- α -methyl- γ -butyrolactone, α -methacryloyloxy- α -methyl- γ -butyrolactone, β -acryloyloxy- γ -butyrolactone, β -methacryloyloxy- γ -butyrolactone, β -methacryloyloxy- α -methyl- γ -butyrolactone and the like.

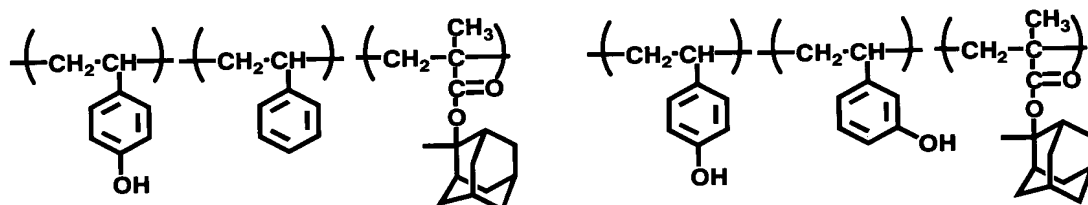
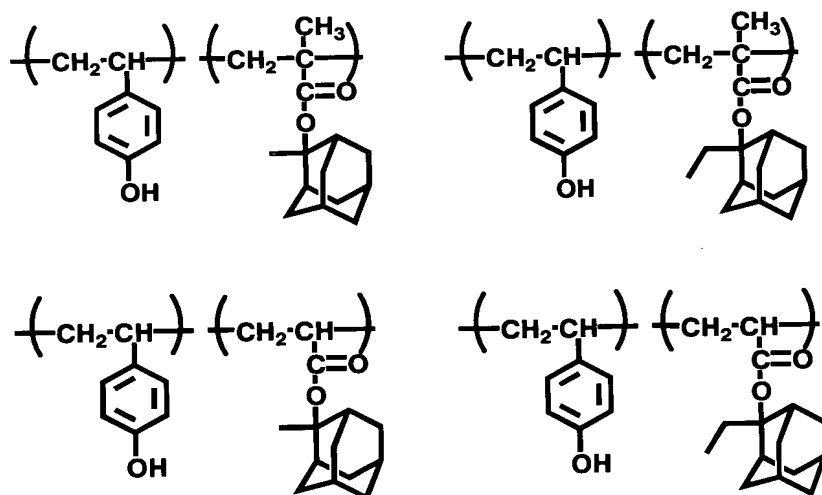
In the case of KrF excimer laser exposure, sufficient transmittance can be obtained even the structural unit derived from hydroxystyrene is contained in the resin. Specifically, copolymerization resins containing a structural unit derived from p- or m-hydroxystyrene as described below are listed. For obtaining such copolymerization resins, the corresponding (meth)acrylic ester monomer can be radical-polymerized with acetoxystyrene and styrene, and then the reaction mixture can be de-acetylated with an acid.

[0047]



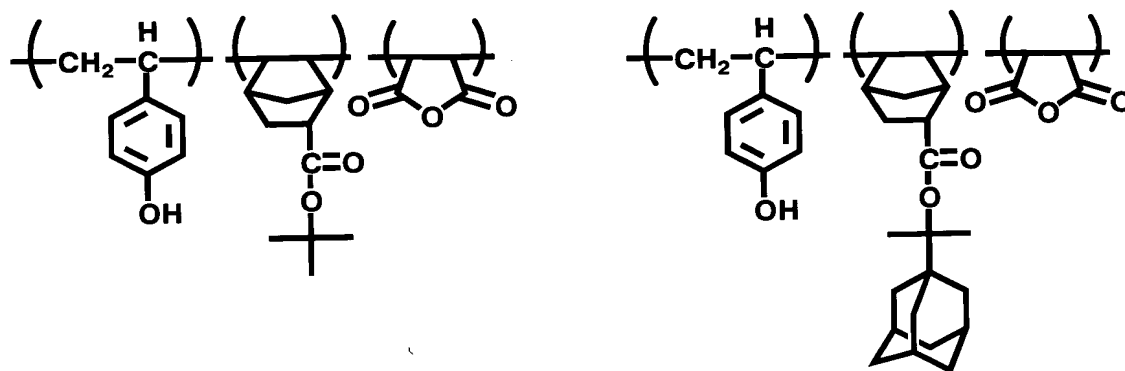


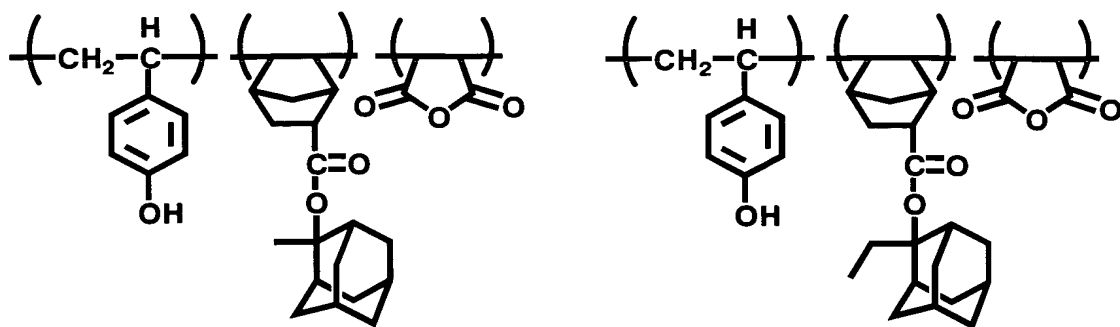
[0048]



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[0049]





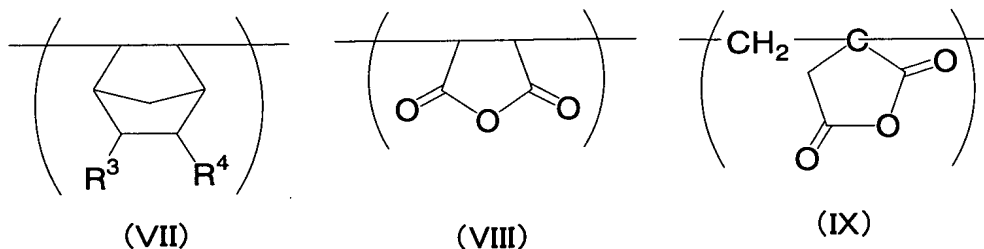
[0050]

In these cases, it is advantageous from the standpoint of dry etching resistance to contain 2-alkyl-2-adamantyl or 1-(1-adamantyl)-1-alkylalkyl as the acid labile group in the resin.

[0051]

The resin containing a structural unit derived from 2-norbornene shows strong structure because of alicyclic group directly present on its main chain and shows a property that dry etching resistance is excellent. The structural unit derived from 2-norbornene can be introduced into the main chain by radical polymerization using, for example, in addition to corresponding 2-norbornene, aliphatic unsaturated dicarboxylic anhydrides such as maleic anhydride and itaconic anhydride together. The structural unit derived from 2-norbornene is formed by opening of its double bond, and can be represented by the formula (VII). The structural unit derived from maleic anhydride and the structural unit derived from itaconic anhydride which are the structural unit derived from aliphatic unsaturated dicarboxylic anhydrides are formed by opening of their double bonds, and can be represented by the formula (VIII) and the formula (IX), respectively.

[0052]



[0053]

Here, R³ and R⁴ in the formula (VII) each independently represent
 5 hydrogen, alkyl having 1 to 3 carbon atoms, hydroxyalkyl having 1 to 3 carbon atoms, carboxyl, cyano or -COOZ group in which Z represents alcohol residue, or R³ and R⁴ can bond together to form a carboxylic anhydride residue represented by -C(=O)OC(=O)-.

In R³ and/or R⁴, examples of the alkyl include methyl, ethyl, propyl and
 10 isopropyl, specific examples of hydroxyalkyl include hydroxymethyl, 2-hydroxyethyl and the like.

In R³ and/or R⁴, -COOZ group is an ester formed from carboxyl, and as
 the alcohol residue corresponding to Z, for example, optionally substituted
 alkyls having about 1 to 8 carbon atoms, 2-oxoxolan-3- or -4-yl and the like are
 15 listed, and as the substituent on the alkyl, hydroxyl, alicyclic hydrocarbon residues and the like are listed.

Specific examples of -COOZ include methoxycarbonyl, ethoxycarbonyl,
 2-hydroxyethoxycarbonyl, tert-butoxycarbonyl, 2-oxoxalan-3-ylloxycarbonyl,
 2-oxoxalan-4-ylloxycarbonyl, 1,1,2-trimethylpropoxycarbonyl,
 20 1-cyclohexyl-1-methylethoxycarbonyl,
 1-(4-methylcyclohexyl)-1-methylethoxycarbonyl,

1-(1-adamantyl)-1-methylethoxycarbonyl and the like.

[0054]

Specific examples of the monomer used to derive the structural unit represented by the formula (VII) may include the followings;

- 5 2-norbornene,
- 2-hydroxy-5-norbornene,
- 5-norbornen-2-carboxylic acid,
- methyl 5-norbornen-2-carboxylate,
- t-butyl 5-norbornen-2-carboxylate,
- 10 1-cyclohexyl-1-methylethyl 5-norbornen-2-carboxylate,
- 1-(4-methylcyclohexyl)-1-methylethyl 5-norbornen-2-carboxylate,
- 1-(4-hydroxycyclohexyl)-1-methylethyl 5-norbornen-2-carboxylate,
- 1-methyl-1-(4-oxocyclohexyl)ethyl 5-norbornen-2-carboxylate,
- 1-(1-adamantyl)-1-methylethyl 5-norbornen-2-carboxylate,
- 15 1-methylcyclohexyl 5-norbornen-2-carboxylate,
- 2-methyl-2-adamantyl 5-norbornen-2-carboxylate,
- 2-ethyl-2-adamantyl 5-norbornen-2-carboxylate,
- 2-hydroxyethyl 5-norbornen-2-carboxylate,
- 5-norbornen-2-methanol,
- 20 5-norbornen-2, 3-dicarboxylic acid anhydride, and the like.

[0056]

The resin used in the present composition preferably contains structural unit(s) having an acid-labile group generally in a ratio of 10 to 80% by mol in all structural units of the resin though the ratio varies depending on the kind of

radiation for patterning exposure, the kind of an acid-labile group, and the like.

When the structural units particularly derived from 2-alkyl-2-adamantyl (meth)acrylate or 1-(1-adamantyl)-1-alkylalkyl (meth)acrylate are used as the acid-labile group, it is advantageous that the ratio of the structural units is 15%
 5 by mol or more in all structural units of the resin.

When, in addition to structural units having an acid-labile group, other structural units not easily dissociated by the action of an acid, for example, a structural unit derived from 3-hydroxy-1-adamantyl (meth)acrylate, a structural units derived from 3,5-dihydroxy-1-adamantyl (meth)acrylate or α
 10 -(meth)acryloyloxy- γ -butyrolactone, a structural units derived from β -(meth)acryloyloxy- γ -butyrolactone, a structural unit of the formula (IIIa) or (IIIb), a structural unit derived from hydroxystyrene, a structural unit of the formula (VII), a structural unit derived from maleic anhydride of the formula (VIII) which is a structural unit derived from an aliphatic unsaturated
 15 dicarboxylic anhydride, a structural unit derived from itaconic anhydride of the formula (IX) and the like are contained, it is preferable that the sum of these structural units is in the range of 20 to 90% by mol based on all structural units of the resin.

[0057]

20 When 2-norbornenes and aliphatic unsaturated dicarboxylic anhydride are used as copolymerization monomer, it is preferable to use them in excess amount in view of a tendency that these are not easily polymerized.

[0058]

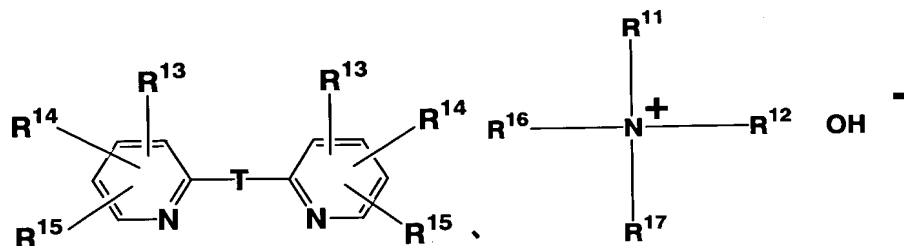
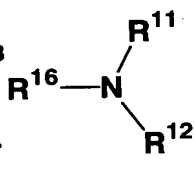
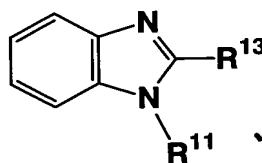
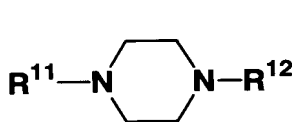
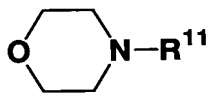
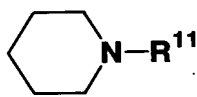
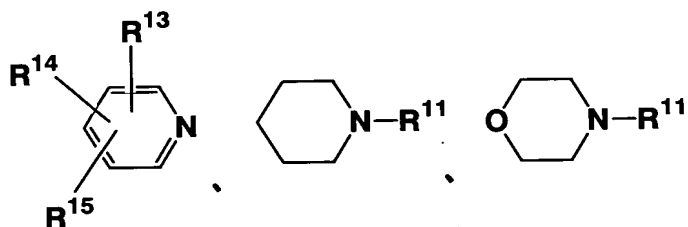
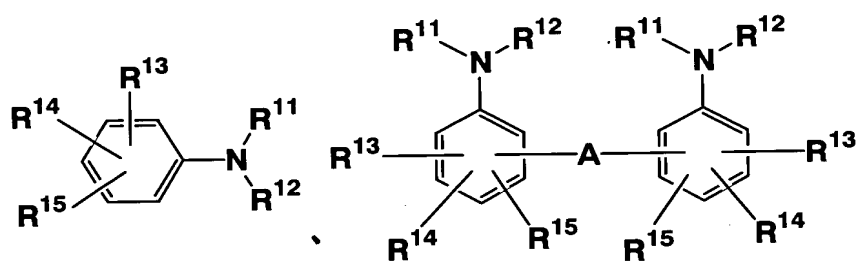
In the present composition, performance deterioration caused by

inactivation of acid which occurs due to post exposure delay can be diminished by adding basic compounds, particularly, basic nitrogen-containing organic compounds, for example, amines as a quencher.

Specific examples of such basic compounds include the ones

5 represented by the following formulae:

[0058]



10

[0060]

Wherein R^{11} , R^{12} and R^{17} each independently represent hydrogen, alkyl, cycloalkyl or aryl. The alkyl, cycloalkyl or aryl may each independently be

substituted by hydroxyl, amino, or alkoxy having 1 to 6 carbon atoms. The amino may be substituted by alkyl having 1 to 4 carbon atoms. The alkyl preferably has about 1 to 6 carbon atoms, the cycloalkyl preferably has about 5 to 10 carbon atoms, and the aryl preferably has about 6 to 10 carbon atoms.

5 R^{13} , R^{14} and R^{15} each independently represent hydrogen, alkyl, cycloalkyl, aryl or alkoxy. The alkyl, cycloalkyl, aryl or alkoxy may each independently be substituted by hydroxyl, amino, or alkoxy having 1 to 6 carbon atoms. The amino may be substituted by alkyl having 1 to 4 carbon atoms. The alkyl preferably has about 1 to 6 carbon atoms, the cycloalkyl preferably has
10 about 5 to 10 carbon atoms, the aryl preferably has about 6 to 10 carbon atoms, and the alkoxy preferably has about 1 to 6 carbon atoms.

R^{16} represents alkyl or cycloalkyl. The alkyl or cycloalkyl may each independently be substituted by hydroxyl, amino, or alkoxy having 1 to 6 carbon atoms. The amino may be substituted by alkyl having 1 to 4 carbon atoms. The
15 alkyl preferably has about 1 to 6 carbon atoms, and the cycloalkyl preferably has about 5 to 10 carbon atoms.

Z represents alkylene, carbonyl, imino, sulfide or disulfide. The alkylene preferably has about 2 to 6 carbon atoms.

Moreover, among $R^{11} - R^{17}$, in regard to those which can be
20 straight-chained or branched, either of these may be permitted.

[0061]

Examples of such compounds include hexylamine, heptylamine, octylamine, nonylamine, decylamine, aniline, 2-, 3- or 4-methylaniline, 4-nitroaniline, 1- or 2-naphtylamine, ethylenediamine, tetramethylenediamine,

- hexamethylenediamine, 4,4'-diamino-1,2-diphenylethane,
 4,4'-diamino-3,3'-dimethyldiphenylmethane,
 4,4'-diamino-3,3'-diethyldiphenylmethane, dibutylamine, dipentylamine,
 dihexylamine, diheptylamine, dioctylamine, dinonylamine, didecylamine,
 5 N-methylaniline, piperidine, diphenylamine, triethylamine, trimethylamine,
 tripropylamine, tributylamine, tripentylamine, trihexylamine, trihexylamine,
 triheptylamine, trioctylamine, trinonylamine, tridecylamine,
 methyldibutylamine, methyldipentylamine, methyldihexylamine,
 methyldicyclohexylamine, methyldiheptylamine, methyldioctylamine,
 10 methyldinonylamine, methyldidecylamine, ethyldibutylamine,
 ethyldipentylamine, ethyldihexylamine, ethyldiheptylamine, ethyldioctylamine,
 ethyldinonylamine, ethyldidecylamine, dicyclohexylmethylamine,
 tris[2-(2-methoxyethoxy)ethyl]amine, triisopropanolamine,
 N,N-dimethylaniline, 2,6-isopropylaniline, imidazole, pyridine,
 15 4-methylpyridine, 4-methylimidazole, bipyridine, 2,2'-dipyridylamine,
 di-2-pyridyl ketone, 1,2-di(2-pyridyl)ethane, 1,2-di(4-pyridyl)ethane,
 1,3-di(4-pyridyl)propane, 1,2-bis(2-pyridyl)ethylene,
 1,2-bis(4-pyridyl)ethylene, 1,2-bis(4-pyridyloxy)ethane, 4,4'-dipyridyl sulfide,
 4,4'-dipyridyl disulfide, 1,2-bis(4-pyridyl)ethylene, 2,2'-dipicolylamine,
 20 3,3'-dipicolylamine, tetramethylammonium hydroxide,
 tetraisopropylammonium hydroxide, tetrabutylammonium hydroxide,
 tetra-n-hexylammonium hydroxide, tetra-n-octylammonium hydroxide,
 phenyltrimethylammonium hydroxide,
 3-(trifluoromethyl)phenyltrimethylammonium hydroxide, choline, and the like.

[0062]

Furthermore, hindered amine compounds having piperidine skeleton as disclosed in JP-A-H11-52575 can be used as quencher.

[0063]

5 It is preferable that the present composition contains resin in an amount of about 80 to 99.9% by weight and the acid generator in an amount of 0.1 to 20% by weight based on the total solid content of the present composition.

 When basic compound is used as a quencher, it is preferable that the basic compound is contained in an amount of about 0.01 to 1% by weight based
10 on the total solid content of the present composition.

 The present composition can contain, if necessary, various additives in small amount such as a sensitizer, solution suppressing agent, other resins, surfactant, stabilizer, dye and the like.

[0064]

15 The present composition is usually in the form of a resist liquid composition in which the aforementioned ingredients are dissolved in a solvent, and the resist liquid composition is to be applied onto a substrate such as a silicon wafer by a conventional process such as spin coating. The solvent used here is sufficient to dissolve the aforementioned ingredients, have an adequate
20 drying rate, and give a uniform and smooth coat after evaporation of the solvent and, hence, solvents generally used in the art can be used.

 Examples thereof include glycol ether esters such as ethylcellosolve acetate, methylcellosolve acetate and propylene glycol monomethyl ether acetate; esters such as ethyl lactate, butyl lactate, amyl lactate and ethyl pyruvate

and the like; ketones such as acetone, methyl isobutyl ketone, 2-heptanone and cyclohexanone; cyclic esters such as γ -butyrolactone, and the like. These solvents can be used each alone or in combination of two or more.

[0065]

5 A resist film applied onto the substrate and then dried is subjected to exposure for patterning, then heat-treated for facilitating a deblocking reaction, and thereafter developed with an alkali developer. The alkali developer used here may be any one of various alkaline aqueous solutions used in the art, and generally, an aqueous solution of tetramethylammonium hydroxide or
10 (2-hydroxyethyl)trimethylammonium hydroxide (commonly known as “choline”) is often used.

 Though the embodiments of the present invention are explained the above, it should be construed that embodiments disclosed here are examples in all aspects and not restrictive. It is intended that the scope of the present invention
15 is determined not by the above descriptions but by appended Claims, and includes all variations of the equivalent meanings and ranges to the Claims.

[0066]

 The present invention will be described more specifically by way of examples, which are not construed to limit the scope of the present invention.
20 The “%” and “part(s)” used to represent the content of any component and the amount of any material used in the following examples are on a weight basis unless otherwise specifically noted. The weight-average molecular weight of any material used in the following examples is a value found by gel permeation chromatography using styrene as a standard reference material.

[0067]

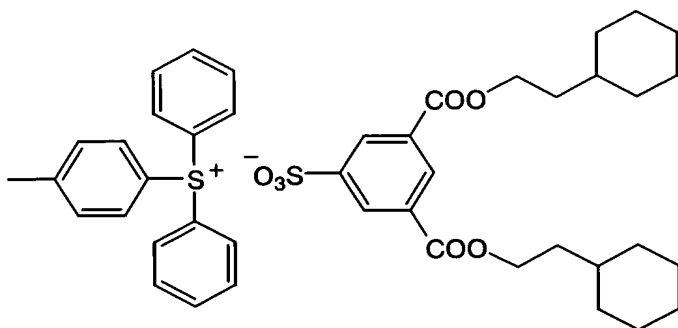
Acid generator synthesis example 1: Synthesis of acid generator B1

Into a flask was charged 6 parts of 5-sulfoisophtalic acid and 50 parts of cyclohexaneethanol, and the mixture was stirred at 135 to 140 °C for 9 hours.

- 5 After cooling, to this was added 50 parts of dimethylsulfoxide, 10 parts of methanol and 200 parts of n-heptane, the mixture was stirred and settled to give two separate layers. After separating the bottom layer from the upper layer, the bottom layer was washed with n-heptane twice. The mixture obtained by correcting the upper layer and two washed n-heptane was concentrated by
- 10 evaporating n-heptane and methanol. To the solution obtained was added 3.0 parts of silver oxide, and the mixture was stirred for 16 hours at room temperature. After filtration, to the filtrate was added dropwise the mixed solution of 8.67 parts of p-tolyldiphenylsulfonium iodide and 86.7 parts of methanol, and then the mixture was stirred for 16 hours at room temperature.
- 15 After filtration, to the filtrate was 200 parts of ethyl acetate, and washed with 100 parts of water 5 times. The organic layer obtained was concentrated. The concentrate was washed with 200 parts of n-heptane and then concentrated, and the washing and concentration was repeated twice. The concentrate was washed with another 200 parts of n-heptane and then washed, concentrated and filtrated
- 20 to obtain 6.24 parts of pale yellow crystals.

It was confirmed that the structure of the crystals was the following formula by NMR ("GX-270" manufactured by JEOL Ltd.) and mass spectrometry (LC analyser is No.1100 manufactured by HP, MASS analyser is LC/MSD manufactured by HP).

[0068]



[0069]

¹H-NMR (chloroform-d, internal standard substance: tetramethylsilane):

5 δ (ppm)

0.94-1.00 (m, 4H); 1.14-1.26 (m, 6H); 1.41-1.44 (m, 2H); 1.62-1.76 (m, 14H);
 2.44 (s, 3H); 4.33 (t, 4H); 7.46 (d, 2H) ; 7.65 – 7.77 (m, 12H) ; 8.61 (s, 1H) ;
 8.77 (d, 2H)

MS (ESI (+) Spectrum): M+ 277.2

10 MS (ESI (-) Spectrum): M- 465.2

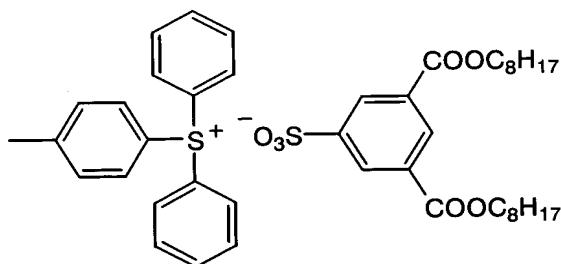
[0070]

Acid generator synthesis example 2: Synthesis of acid generator C1

The reactions and post treatments were conducted in the same manner as
 in Acid generator synthesis example 1 except that n-octanol was used instead of
 15 cyclohexaneethanol, and yellow oil product was obtained.

It was confirmed that the structure of the oil product was the following
 formula by NMR (“GX-270” manufactured by JEOL Ltd.) and mass
 spectrometry (LC analyser is No.1100 manufactured by HP, MASS analyser is
 LC/MSD manufactured by HP).

20 [0071]



[0072]

¹H-NMR (chloroform-d, internal standard substance: tetramethylsilane):

δ (ppm)

5 0.89 (t, 6H); 1.19-1.39 (m, 20H); 1.72(dd, 4H) ; 2.44 (s, 3H) ; 4.29 (t, 4H); 7.46 (d, 2H); 7.62–7.77 (m, 12H); 8.62 (s, 1H) ; 8.79 (d, 2H)

MS (ESI (+) Spectrum): M+ 277.2

MS (ESI (-) Spectrum): M- 469.2

[0073]

10 2-Ethyl-2-adamantyl methacrylate,

5-methacryloyloxy-2,6-norbornenelactone and

α-methacryloyloxy-γ-butyrolactone were charged at a molar ratio of 35:40:25 (12.42 g:12.70 g:5.58 g), and equal weight amount (30.70 g) to all monomers of 1,4-dioxane was added, and then was added 3mol% (0.70 g) based on all

15 monomers of azobisisobutyronitrile as an initiator to prepare solution. In another flask, one and a half times by weight (46.04 g) to all monomers of

1,4-dioxane was charged and heated to 87 °C. To this was added the solution obtained above over one hour and the mixture was stirred for 5 hours

maintaining the temperature. Then, operation of pouring into large amount of

20 n-heptane to cause crystallization was repeated three times for purification, and then dried to obtain 25.4 g (Yield: 82.7%) of copolymer having an average

molecular weight of 8900. This is called resin A1.

[0074]

Next, resist compositions were prepared by mixing raw materials shown below in addition to the resins obtained in the above-mentioned resins, and

5 filtrating through a fluorine resin filter having pore diameter of 0.2 μm .

[0075]

<Acid generator>

B1: 4-methylphenyldiphenylsulfonium 3,5-bis(2-cyclohexylethoxycarbonyl)-benzenesulfonate

10 C1: 4-methylphenyldiphenylsulfonium 3,5-bis(n-octyloxycarbonyl)-benzenesulfonate

<Quencher>

D1: 2,6-diisopropylaniline

<Solvent>

15	E1: propyleneglycol monomethyl ether acetate	26 parts
	2-heptanone	26 parts
	γ -butyrolactone	3 parts

[0076]

Example 1 and Comparative Example 1

20 Resin (kind and amount are described in Table 1)

Acid generator (kind and amount are described in Table 1)

Quencher (kind and amount are described in Table 1)

Solvent (kind and amount are described in Table 1)

[0077]

Silicon wafers were each coated with "ARC-29A-8", which is an organic anti-reflective coating composition available from Brewer Co., and then baked under the conditions: 215°C, 60 seconds, to form a 780Å-thick organic anti-reflective coating. Each of the resist liquids prepared as above was spin-coated over the anti-reflective coating so that the thickness of the resulting film became 0.30μm or 0.25μm after drying. The silicon wafers thus coated with the respective resist liquids were each prebaked on a direct hotplate at temperature shown in "PB" column in Table 1 for 60 seconds. Using an ArF excimer stepper ("NSR ArF" manufactured by Nikon Corporation, NA=0.55, 2/3 Annular), each wafer thus formed with the respective resist film was subjected to line and space pattern exposure, with the exposure quantity being varied stepwise.

After the exposure, each wafer was subjected to post-exposure baking on a hotplate at temperature shown in "PEB" column in Table 1 for 60 seconds and then to paddle development for 60 seconds with an aqueous solution of 2.38wt% tetramethylammonium hydroxide.

A bright field pattern developed on the organic anti-reflective coating substrate was observed with a scanning electron microscope, the results of which are shown in Table 2. The term "bright field pattern", as used herein, means a pattern obtained by exposure and development through a reticle comprising an outer frame made of a chromium layer (light-shielding layer) and linear chromium layers (light-shielding layers) formed on a glass surface (light-transmitting portion) extending inside the outer frame. Thus, the bright field pattern is such that, after exposure and development, resist layer

surrounding the line and space pattern is removed while resist layer corresponding to the outer frame is left on the outer side of the region from which the resist layer is removed.

[0078]

- 5 **Effective sensitivity:** It is expressed as the amount of exposure that the line and space pattern having $0.13\mu\text{m}$ become 1:1.

Resolution: It is expressed as the minimum size of line and space pattern split at the exposure amount of the effective sensitivity.



[0079]

10 [Table 1]

Example No.	Resin (Parts)	Acid generator (Part)	Quencher (Part)	Sol-vent	PB	PEB
Example 1	A1/10	B1/0.27	D1/0.0075	E1	140°C	125°C
Comparative example 1	A1/10	C1/0.27	D1/0.0075	E1	140°C	125°C

[0080]

[Table 2]

Example No.	Effective Sensitivity (mJ/cm^2)	Resolution (μm)	Configuration of Resist
Example 1	23	0.12	
Comparative example 1	18	0.12	

[0081]

[Effects of the Invention]

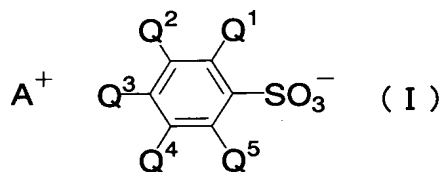
The salt of the present invention is energy-active, and can be suitably used as a component in a resist. The chemical amplification type positive resist composition of the present invention has various good resist abilities such as sensitivity, resolution, and the like, and particularly gives remarkably improved line edge roughness, and pattern profiles thereof are also good. Therefore, it is suitable for excimer laser lithography using ArF, KrF and the like, has large industrial values.

[DOCUMENT NAME] Abstract

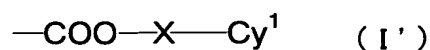
[ABSTRACT]

[PROBLEM] To provide a novel salt and to provide a chemical amplification type positive resist showing excellent various resist abilities such as sensitivity,
 5 resolution and the like, and giving particularly improved line edge roughness and pattern profiles.

[SOLVING MEANS] [1] A salt of the formula (I):



wherein Q^1 , Q^2 , Q^3 , Q^4 and Q^5 each independently represent hydrogen,
 10 optionally branched alkyl having 1 to 16 carbon atoms, optionally branched alkoxy having 1 to 16 carbon atoms, halogen, aryl having 6 to 12 carbon atoms, aralkyl having 7 to 12 carbon atoms, cyano, sulfide, hydroxy, nitro or a group of the formula (I')



15 wherein X represents linear alkyl or linear alkyl optionally containing thioether bond or ether bond, and Cy^1 represents alicyclic hydrocarbon group having 3 to 20 carbon atoms,
 and A^+ represents a counter ion, with the proviso that at least one of Q^1 , Q^2 , Q^3 , Q^4 and Q^5 is the group of the formula (I').

20 [2] A chemical amplification type positive resist composition comprising resin which has a structural unit having an acid labile group and which itself is insoluble or poorly soluble in an alkali aqueous solution but becomes soluble in

an alkali aqueous solution by the action of an acid, and a salt described in [1].

[SELECTED DRAWING] None